

**REQUEST
FOR
CONTINUED EXAMINATION (RCE)
TRANSMITTAL**

Subsection (b) of 35 U.S.C. § 132, effective on May 29, 2000, provides for continued examination of an utility or plant application filed on or after June 8, 1995. See The American Inventors Protection Act of 1999 (AIPA).

Application Number	09/315,988
Filing Date	May 21, 1999
Examiner Name	Kalimah Fernandez
First Named Inventor	Hajime Kawano, et al.
Group Art Unit	2881
Attorney Docket Number	29273/502

This is a Request for Continued Examination (RCE) under 37 C.F.R. § 1.114 of the above-identified application.

NOTE: 37 C.F.R. § 1.114 is effective on May 29, 2000. If the above-identified application was filed prior to May 29, 2000, applicant may wish to consider filing a continued prosecution application (CPA) under 37 C.F.R. § 1.53 (d) (PTO/SB/29) instead of a RCE to be eligible for the patent term adjustment provisions of the AIPA. See Changes to Application Examination and Provisional Application Practice, Interim Rule, 65 Fed. Reg. 14865 (Mar. 20, 2000), 1233 Off. Gaz. Pat. Office 47 (Apr. 11, 2000), which established RCE practice.

1. Submission required under 37 C.F.R. § 1.114

- a. ☐ Previously submitted
- i. ☐ Consider the amendment(s)/reply under 37 C.F.R. § 1.116 previously filed on (Any unentered amendment(s) referred to above will be entered).
- ii. ☐ Consider the arguments in the Appeal Brief or Reply Brief previously filed on
- iii. ☐ Other
- b. Enclosed
- i. ☒ Amendment/Reply
- ii. ☐ Affidavit(s)/Declaration(s)
- iii. ☐ Information Disclosure Statement (IDS)
- iv. ☐ Other

2. Miscellaneous

- a. ☐ Suspension of action on the above-identified application is requested under 37 C.F.R. § 1.103(c) for a period of _____ months. (Period of suspension shall not exceed 3 months; Fee under 37 C.F.R. § 1.17(i) required)
- b. ☐ Other

3. Fees The RCE fee under 37 C.F.R. § 1.17(e) is required by 37 C.F.R. § 1.114 when the RCE is filed.

- a. ☒ The Director is hereby authorized to charge the following fees, or credit any overpayments, to Deposit Account No. 11-0600
- i. ☒ RCE fee required under 37 C.F.R. § 1.17(e)
- ii. ☐ Extension of time fee (37 C.F.R. §§ 1.136 and 1.17)
- iii. ☐ Other
- b. ☐ Check in the amount of \$ _____ enclosed
- c. ☐ Payment by credit card (Form PTO-2038 enclosed)

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SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT REQUIRED

Name (Print /Type)	David J. Zibelli	Registration No. (Attorney/Agent)	36,394
Signature	<i>David J. Zibelli</i>	Date	December 11, 2003

CERTIFICATE OF MAILING OR TRANSMISSION

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner For Patents, Box RCE, Washington, DC 20231, or facsimile transmitted to the U.S. Patent and Trademark Office on:

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Signature	Date

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RESPONSE UNDER 37 C.F.R. § 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 2881

PATENT
DKT. NO.: 29273/502

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS : Hajime KAWANO, et al.
SERIAL NO. : 09/315,988
FILED : May 21, 1999
FOR : ELECTRON BEAM LITHOGRAPHY SYSTEM
GROUP ART : 2881
EXAMINER : Kalimah Fernandez

COMMISSIONER FOR PATENTS
P.O. BOX 1450
Alexandria, VA 22313-1450

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AMENDMENT

Sir:

In response to the office action dated July 11, 2003, the due date being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS

Please amend claims 1-3 and 8-10 as follows:

1. (Currently Amended) An electron beam lithography system comprising:
an exposure map creating means unit which, based on positional relations between meshes dividing a region to be rendered by an electron beam on the one hand and shots to be rendered by said electron beam on the other hand, creates an exposure map by calculating an area density from a shot area included in each of said meshes; and